

WHAT IS CLAIMED IS:

1. A particle-measuring system,  
provided in a processing system for generating an  
atmosphere including atmospheric air or a gas exhausted  
5 from within a processing chamber by a vacuum pump, and  
for processing an object relating to a semiconductor  
manufacturing in this atmosphere, and

installed on an exhaust pipe that connects between  
an exhaust opening of the processing chamber and the  
10 vacuum pump, for measuring the number of particles  
included in the exhaust gas.

2. The particle-measuring system according to  
claim 1, comprising:

a laser beam irradiator for irradiating laser  
15 beams to within the exhaust pipe along a line  
connecting between a center point of a cross section of  
the exhaust pipe and a center axis passing vertically  
through a center of the processing chamber; and

a scattered light detector provided in a direction  
20 approximately orthogonal with an irradiation direction  
of the laser beams, for detecting scattered lights from  
the particles.

3. The particle-measuring system according to  
claim 2, wherein

25 the laser beam irradiator irradiates laser beams  
onto a portion of high density of particles included in  
an exhaust gas exhausted from within the exhaust pipe,

00790 644560

and

the scattered light detector directs a detection direction to the portion of high density of particles included in the exhaust gas exhausted from within the exhaust pipe, in a direction approximately orthogonal with the irradiation direction of the laser beams.

4. The particle-measuring system according to claim 2, wherein

a center of the scattered light detector is set to direct to a point offset by a predetermined distance from the center point of the cross section of the exhaust pipe in a direction opposite to a direction in which the center axis passing vertically through the center of the processing chamber is positioned.

5. The particle-measuring system according to claim 1, comprising:

a laser beam irradiator for irradiating laser beams so that the laser beams are transmitted through a point offset by a predetermined distance from the center point of the cross section of the exhaust pipe in a direction opposite to a direction in which the center axis passing vertically through the center of the processing chamber is positioned; and

a scattered light detector provided in a direction approximately orthogonal with an irradiation direction of the laser beams, for detecting scattered lights from the particles.

6. The particle-measuring system according to claim 4, wherein

a maximum value of the predetermined offset distance is 0.75 times the radius of the exhaust pipe.

5 7. The particle-measuring system according to claim 5, wherein

a maximum value of the predetermined offset distance is 0.75 times the radius of the exhaust pipe.

10 8. The particle-measuring system according to claim 1, wherein the exhaust pipe is installed at a position

where light generated within the processing chamber do not reach position, a distance from the processing chamber is minimum, and there are high and low densities of particle included in the exhaust gas within the exhaust pipe.

15 9. A particle-measuring method for measuring the number of particles included in an exhaust gas exhausted from a processing system for generating an atmosphere including atmospheric air or a gas exhausted from within a processing chamber by a vacuum pump, and for processing an object relating to a semiconductor manufacturing in this atmosphere,

20 the method comprising the steps of:  
25 modeling parameters;

carrying out a numerical simulation for expressing trajectory of an exhaust gas that includes particles

004490" 62446560

flowing through an exhaust pipe;

carrying out a trajectory numerical simulation of  
an exhaust gas and particles;

confirming an optimum position for measuring  
5 particles;

determining sensor installation position;

installing the sensor; and

evaluating a measurement of particle,

wherein trajectory of particles that flow through  
10 the exhaust pipe after the particles have been  
generated inside the processing chamber and exhausted  
from the processing chamber are simulated, to select an  
area where the density of the particles is the highest  
in the radial direction of the exhaust pipe, a laser  
15 beam irradiator is disposed at a position in this area  
where laser beams for measurement pass through, and a  
scattered light detector is disposed in a direction  
orthogonal with the laser beams, thereby to measure the  
particles.

20 10. The particle-measuring method according to  
claim 9, wherein

the step of modeling parameters comprises the  
steps of:

25 modeling an exhaust configuration based on a shape  
of the chamber, a configuration of the exhaust pipe and  
a piping layout of the exhaust pipe;

modeling processing conditions including a kind of

004490" 6244550

a gas, a pressure, a flow rate, and temperature;

modeling particle conditions including a composition, a density and sizes of particles generated; and

5 modeling constructional members and a position for generating the particles.

11. The particle-measuring method according to claim 9, wherein the trajectory numerical simulation is obtained based on the number of openings of exhaust  
10 pipes provided in the chamber, their shapes, their layout positions, and a flow rate of the exhaust gas.

12. A particle-measuring system, provided in a processing system for generating an atmosphere including atmospheric air or a gas exhausted from  
15 within a processing chamber by a vacuum pump, and for processing an object relating to a semiconductor manufacturing in this atmosphere,

the particle-measuring system comprising:

a sensor manifold installed in air-tight in front  
20 of the vacuum pipe in the middle of the exhaust pipe connected to the processing chamber, and having a rotating mechanism;

a laser beam irradiator installed on the sensor manifold, and having a driving mechanism movable in a  
25 radial direction of the exhaust pipe;

a beam stopper installed on the sensor manifold opposite to the laser beam irradiator, and having a

004790" 62446560

driving mechanism movable in a direction to face straight the laser beam irradiator, for receiving irradiated laser beams; and

5 a scattered light detector installed on the sensor manifold in a direction approximately orthogonal with the irradiation direction of the laser beams, and having a driving mechanism movable in two-dimensional directions, for detecting the laser light scattered by the particles;

10 a position controller for operating the driving mechanisms of the laser beam irradiator and the beam stopper so that the laser beams pass through an area in which the density of the particles is high in the sensor manifold assumed by simulation, and for moving  
15 the scattered light detector to a position for detecting scattered lights from the high-density area; and

a controller/processor for controlling the laser beam irradiator and the scattered light detector and  
20 for processing a measurement result obtained.

13. The particle-measuring system according to claim 12, wherein each driving mechanism has a motor or a linear motor as a driving source.

14. The particle-measuring system according to  
25 claim 12, wherein the sensor manifold is connected in airtight to the exhaust pipe so as to be rotatable around the exhaust pipe by a magnetic fluid seal.

004790 6246560

15. A particle-measuring method for measuring the number of particles included in an exhaust gas exhausted from a processing system for generating an atmospheric air or a process gas exhausted from within a processing chamber by a vacuum exhaust system, and for processing an object relating to a semiconductor manufacturing in this atmosphere, the particle measuring method using a system having a laser irradiator, a scattered light detector and a beam stopper for measuring the number of particles by irradiating laser beams to particles generated within the processing chamber,

the particle-measuring method comprising the steps of:

selecting an area in which the density of particles is high by carrying out a simulation based on information on constructional members including the processing chamber and other members disposed inside the processing chamber, information on the vacuum exhaust system, and information on the process gas;

adjusting a position of the laser beam irradiator so that the laser beam irradiator can irradiate laser beams in an area in which the density of particles is high based on the simulation;

adjusting a position of the beam stopper to face the laser irradiator so that the beam stopper can receive laser beams passed through the high-density

09594479 "061400

area;

adjusting a position of the scattered light  
detector so that the scattered light detector can  
detect scattered lights of the laser beams passed  
5 through the high-density area;

irradiating by the laser irradiator the laser  
beams to an area in which the density of particles is  
high;

detecting by the scattered light detector the  
10 scattered lights of the laser beams passed through the  
high-density area; and

calculating the number of particles from the  
scattered lights detected.

16. A particle-measuring method for measuring the  
15 number of particles included in an exhaust gas  
exhausted from a processing system for generating an  
atmospheric air or a gas exhausted from within a  
processing chamber by vacuum exhausting, the particle  
measuring method for measuring particles using a  
20 particle-measuring system having a laser position  
adjusting unit,

the particle-measuring method comprising the steps  
of:

determining an optimum position of installing a  
25 sensor by simulation, and inputting the installation  
position information to a position controller of the  
laser position adjusting unit;

00490 6246560



inputting processing conditions to the position  
controller of the laser position-adjusting unit;

adjusting by the position controller a laser beam  
irradiator, a scattered light detector, a beam stopper  
5 and a sensor manifold to optimum positions  
respectively; and

measuring by the sensor particles generated within  
the processing chamber.

17. The particle-measuring system according to  
10 claim 1, wherein processing chamber has a wall, the  
exhaust opening is made in a given part of the wall,  
the exhaust pipe extends horizontally, vertically or  
slantwise, and a trajectory of particles is simulated  
with respect to a direction in which air or gas is  
15 exhausted through the exhaust pipe.

004790" 6244550